

Machine learning for predictive electrical performance using OCD (Erratum)

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[Proceedings Volume 10959, Metrology, Inspection, and Process Control for Microlithography XXXIII](https://doi.org/10.1117/12.2515806); 109590F (2019) <https://doi.org/10.1117/12.2515806>

Event: Advanced Lithography, 2019, San Jose, California, United States

Online Publication Date: 26 March 2019

Erratum Published: 25 June 2019

A revised version of this manuscript was published on 25 June 2019. Details of the revision are provided below. The original paper has been updated.

This article “Proceedings Volume 10959, Metrology, Inspection, and Process Control for Microlithography XXXIII; 109590F (2019)” was originally published on 26th March 2019 with an error in the slope value in Figure 9c which has been now been corrected.

As a result, this sentence was modified in the new manuscript:

“It was found that there is a good correlation between the capacitance values calculated using the parameters obtained from the OCD model and the measured capacitance value”

The correction does not affect any qualitative or quantitative results and conclusions.